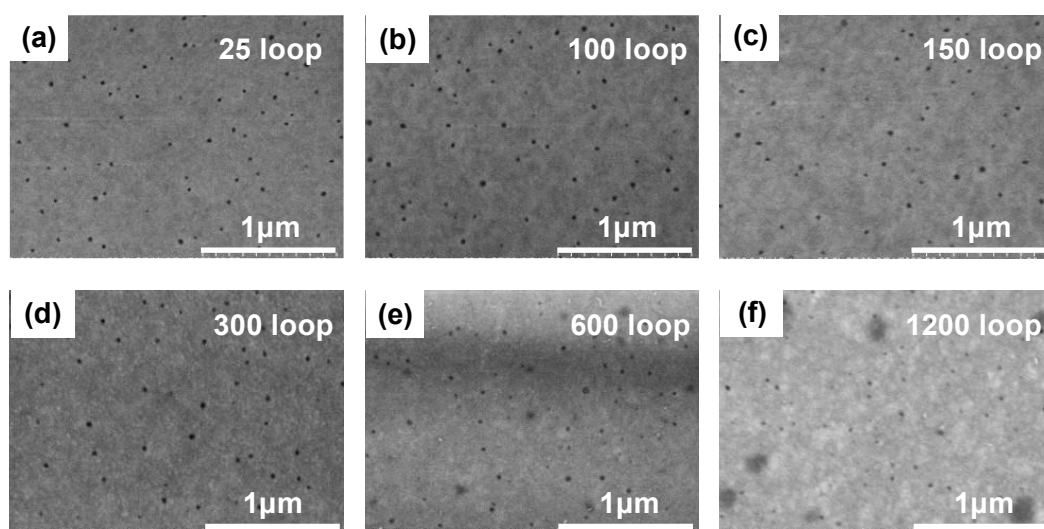
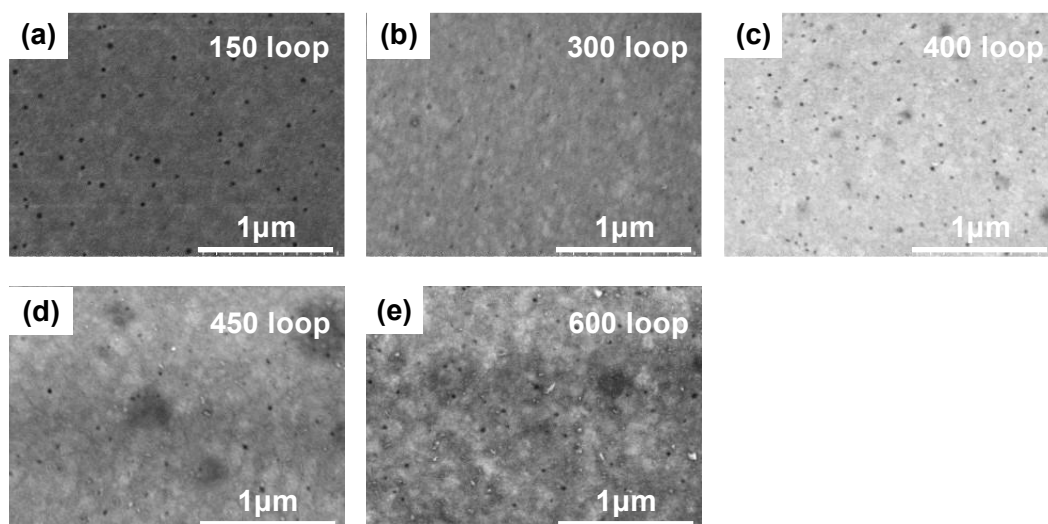


## Effect of the growth interruption on the surface morphology and crystalline quality of MOCVD-grown h-BN

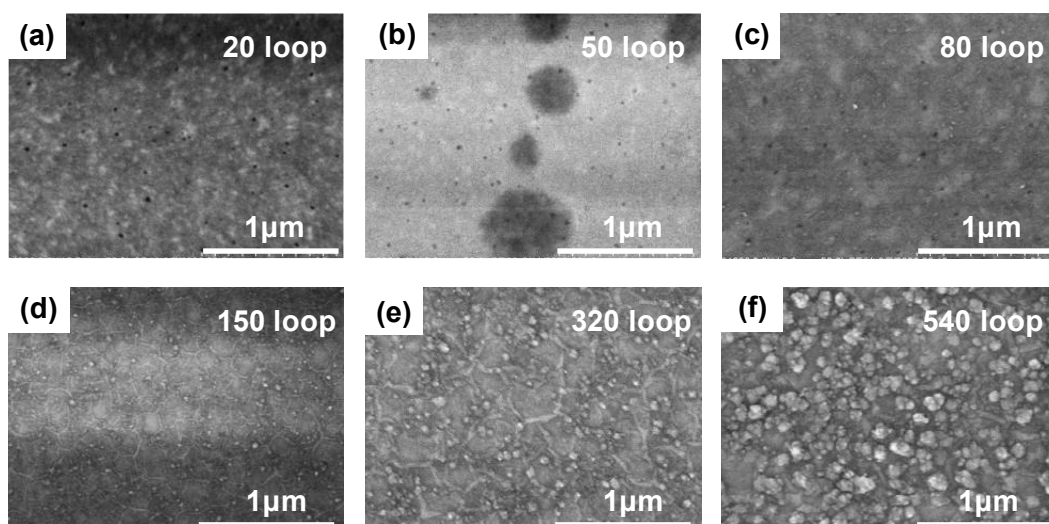
Qi Zhang <sup>1,2</sup>, Yanan Guo <sup>1,2,3,\*</sup>, Zhibin Liu <sup>1,2,3</sup>, Dadi Wang <sup>1,2</sup>, Qiang Li <sup>4</sup>, Jianchang Yan <sup>1,2,3,\*</sup>, Jinmin Li <sup>1,2,3</sup>, and Junxi Wang <sup>1,2,3,\*</sup>



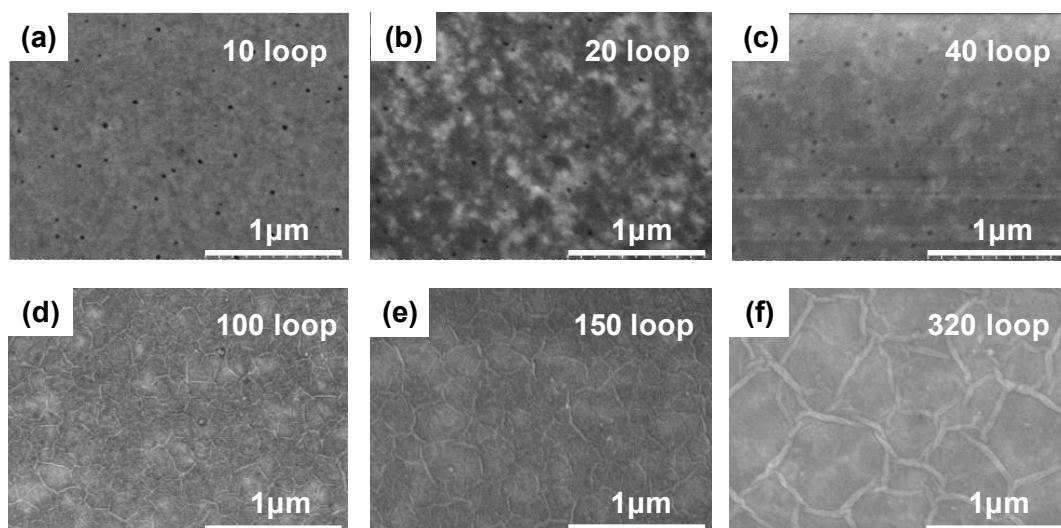
**Figure S1** The surface morphology variations of h-BN films grown by NH<sub>3</sub>/TEB with the growth loops.



**Figure S2** The surface morphology variations of h-BN films grown by NH<sub>3</sub>/Itrp/TEB with the growth loops.

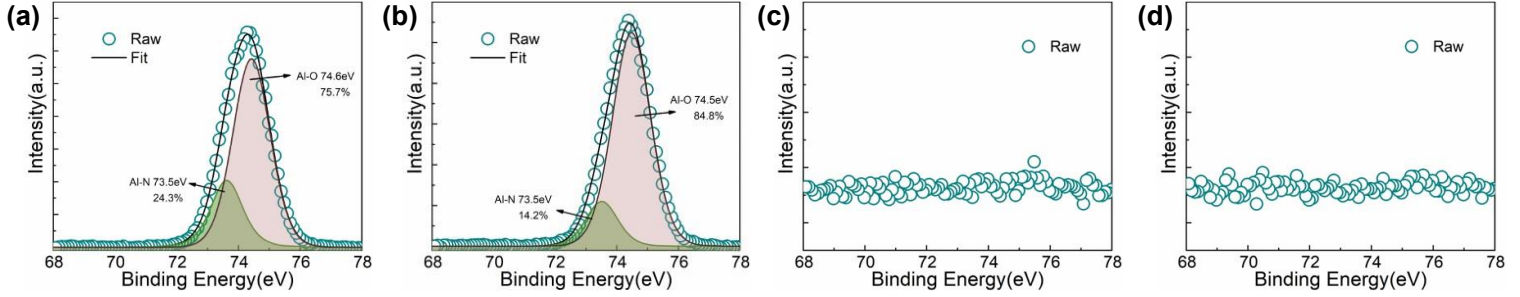


**Figure S3** The surface morphology variations of h-BN films grown by  $\text{NH}_3/\text{TEB}/\text{Itrp}$  with the growth loops.



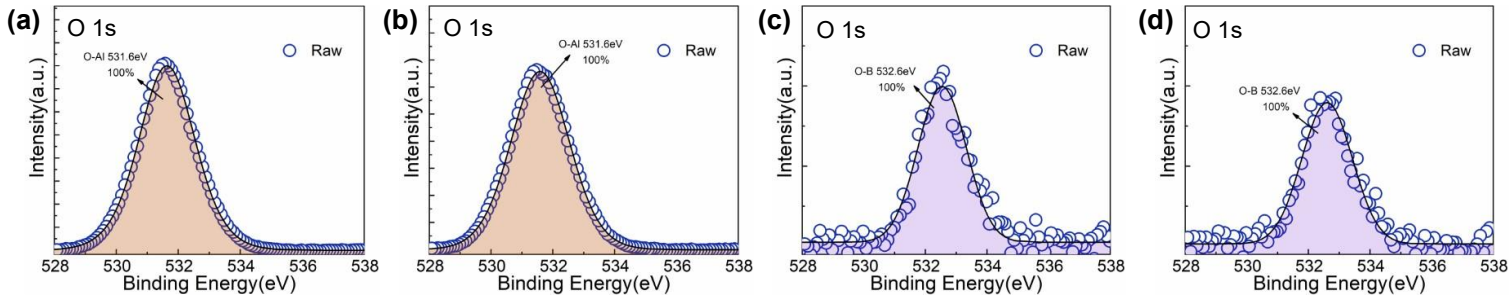
**Figure S4** The surface morphology variations of h-BN films grown by  $\text{NH}_3/\text{Itrp} / \text{TEB}/\text{Itrp}$  with the growth loops.

The HR XP spectra pertaining to Al for the four samples can be seen in figures 6(a)–(d). For the samples using the modes of  $\text{NH}_3/\text{TEB}$  and  $\text{NH}_3/\text{Itrp}/\text{TEB}$ , the peak comprises of two main peaks pertaining to Al-O and Al-N bonds: the Al-O bonds derived from the sapphire substrate signal and the Al-N bonds contributed by the nitrified sapphire. It implies that the BN films grown under  $\text{NH}_3/\text{TEB}$  and  $\text{NH}_3/\text{Itrp}/\text{TEB}$  modes are very thin. There was no substrate dependent Al signal detected due to the thick BN film by  $\text{NH}_3/\text{TEB}/\text{Itrp}$  and  $\text{NH}_3/\text{Itrp}/\text{TEB}/\text{Itrp}$  modes.



**Figure S5** The XPS spectra of Al 2p peak in h-BN film under four FME modes [41]. (a)  $\text{NH}_3/\text{TEB}$ , (b)  $\text{NH}_3/\text{Itrp}/\text{TEB}$ , (c)  $\text{NH}_3/\text{TEB}/\text{Itrp}$ , (d)  $\text{NH}_3/\text{Itrp}/\text{TEB}/\text{Itrp}$ .

As shown in Figure S7, the highly symmetric O 1s core-level spectra is observed for all samples. For the  $\text{NH}_3/\text{TEB}$  and  $\text{NH}_3/\text{Itrp}/\text{TEB}$  modes, the peak is the signal for O-Al bonds. This corresponds to the Al-O bonds in Al 2p. For the  $\text{NH}_3/\text{TEB}/\text{Itrp}$  and  $\text{NH}_3/\text{Itrp}/\text{TEB}/\text{Itrp}$  modes, the peak is assigned to O-B bonds. This corresponds to the B-O bonds in B 1s. It comes from the incorporation of O impurities due to the fast growth rate.



**Figure S6** The XPS spectra of O 1s peak in h-BN film under four FME modes [41,46]. (a)  $\text{NH}_3/\text{TEB}$ , (b)  $\text{NH}_3/\text{Itrp}/\text{TEB}$ , (c)  $\text{NH}_3/\text{TEB}/\text{Itrp}$ , (d)  $\text{NH}_3/\text{Itrp}/\text{TEB}/\text{Itrp}$ .

**Table S1.** The variations of binding energy, FWHM and percentage content of different bonds of B 1s, N 1s and C 1s XPS core level spectra in h-BN films by four FME modes.

B-N				B-O			B-C		
150loop	Position(eV)	FWHM(eV)	B-N%	Position(eV)	FWHM(eV)	B-O%	Position(eV)	FWHM(eV)	B-C%
NH <sub>3</sub> /TEB	190.64	1.15	100	/	/	0	/	/	0
NH <sub>3</sub> /Itrp/TEB	190.68	1.17	100	/	/	0	/	/	0
NH <sub>3</sub> /TEB/Itrp	190.43	0.97	76.0	191.10	0.97	20.6	189.39	0.87	3.4
NH <sub>3</sub> /Itrp/TEB/Itrp	190.50	1.04	75.2	191.29	1.00	12.1	189.69	1.09	12.7

N-B				N-Al			N-O		
150loop	Position(eV)	FWHM(eV)	N-B%	Position(eV)	FWHM(eV)	N-Al%	Position(eV)	FWHM(eV)	N-O%
NH <sub>3</sub> /TEB	398.32	1.20	65.1	397.17	1.24	34.9	/	/	0
NH <sub>3</sub> /Itrp/TEB	398.25	1.24	81.7	369.98	1.19	14.9	400.11	1.43	3.4
NH <sub>3</sub> /TEB/Itrp	398.20	1.19	100	/	/	0	/	/	0
NH <sub>3</sub> /Itrp/TEB/Itrp	398.16	1.19	100	/	/	0	/	/	0

C-C				C-B			C-N		
150loop	Position(eV)	FWHM(eV)	C-C%	Position(eV)	FWHM(eV)	C-B%	Position(eV)	FWHM(eV)	C-N%
NH <sub>3</sub> /TEB	284.8	1.20	81.1	/	/	0	286.17	1.52	9.5
NH <sub>3</sub> /Itrp/TEB	284.8	1.18	82.1	/	/	0	286.00	1.86	9.4
NH <sub>3</sub> /TEB/Itrp	284.8	1.18	84.5	282.57	1.45	5.8	286.31	1.94	9.7
NH <sub>3</sub> /Itrp/TEB/Itrp	284.8	1.28	79.2	282.47	1.28	12.7	286.58	1.30	8.2